

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	3	"20030040173"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 11:54
L3	3	L2	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 13:22
L4	3	3 and electrode	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 11:55
L5	2	3 and electrode with (resist\$4 insulat\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 11:55
L6	2	3 and electrode with (resist\$4 insulat\$4) with form\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 11:56
L7	2	3 and (electrode with (resist\$4 insulat\$4) with form\$4) and sacrific\$9	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 11:57
L8	2	3 and (electrode with (resist\$4 insulat\$4) with form\$4) and (sacrific\$9 with pattern\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:01
L9	7	(organic near2 molecular) and (electrode with (resist\$4 insulat\$4) with form\$4) and (sacrific\$9 with pattern\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:00
L10	39	((organic near2 molecular) (micro adj scale) (nano adj scale)) and (electrode with (resist\$4 insulat\$4) with form\$4) and (sacrific\$9 with pattern\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:35

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L11	0	3 and (electrode with (resist\$4 insulat\$4) with form\$4) and (sacrific\$9 with pattern\$4) and photoetch\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:01
L12	0	3 and (electrode with (resist\$4 insulat\$4) with form\$4) and (sacrific\$9 with pattern\$4) and photo adj etch\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:02
L13	2	3 and (electrode with (resist\$4 insulat\$4) with form\$4) and (sacrific\$9 with pattern\$4) and etch\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:03
L14	0	3 and (electrode with (resist\$4 insulat\$4) with form\$4) and (sacrific\$9 with pattern\$4) and etch\$4 and (pattern\$4 with (line width))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:04
L15	0	3 and (electrode with (resist\$4 insulat\$4) with form\$4) and (sacrific\$9 with pattern\$4) and etch\$4 and (pattern\$4 with polymer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:05
L16	2	3 and (electrode with (resist\$4 insulat\$4) with form\$4) and (sacrific\$9 with pattern\$4) and etch\$4 and polymer	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:05
L17	2	3 and (electrode with (resist\$4 insulat\$4) with form\$4) and (sacrific\$9 with pattern\$4) and etch\$4 same polymer	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:06
L18	2	3 and (electrode with (resist\$4 insulat\$4) with form\$4) and (sacrific\$9 with pattern\$4) and etch\$4 same polymer and (electron with beam)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:15
L19	2	3 and (electrode with (resist\$4 insulat\$4) with form\$4) and (sacrific\$9 with pattern\$4) and etch\$4 same polymer and (electron with beam) and pattern\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:16

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L20	2	3 and (electrode with (resist\$4 insulat\$4) with form\$4) and (sacrific\$9 with pattern\$4) and etch\$4 same polymer and (electron with beam) and (metal near3 electrode)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:16
L21	18	10 and (electron near3 beam)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:34
L22	29	((organic near2 molecular) (micro adj scale) (nano adj scale)) and (electrode with (resist\$4 insulat\$4) with form\$4) and ((sacrific\$9 polymer\$3) with pattern\$4 with (electron beam laser))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 13:01
L23	27	((organic near2 molecular) (micro adj scale) (nano adj scale)) and (electrode with (resist\$4 insulat\$4) with form\$4) and ((sacrific\$9 polymer\$3) with pattern\$4 with (electron laser))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:37
L24	11	((organic near2 molecular) (micro adj scale) (nano adj scale)) and (electrode with (resist\$4 insulat\$4) with form\$4) and ((sacrific\$9 polymer\$3) with (pattern\$4 remov\$4 ablat\$4) with ((electron laser) near2 beam))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:38
L25	57	(polymer\$4 near5 pattern\$4) with (line wide width dimension size) with (nm nanometer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:40
L26	1	24 and 25	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:39
L27	8506	pattern\$4 with (line wide width dimension size) with (nm nanometer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:42
L28	57	25 and 27	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:41

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L29	2	24 and 27	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:41
L30	72	pattern\$4 with (line wide width dimension size) with (nm nanometer) same ((laser electron) near5 beam) and ((organic molecular) near5 (device apparatus))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:56
L31	1	24 and 30	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:56
L32	155	pattern\$4 with (line wide width dimension size) same (nm nanometer) same ((laser electron) near5 beam) and ((organic molecular) near5 (device apparatus))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:57
L33	1	24 and 32	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:57
L34	128	pattern\$4 with (line wide width dimension size) same (organic molecular) same (nm nanometer) same ((laser electron) near5 beam)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:59
L35	0	24 and 34	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:59
L36	2042	pattern\$4 with (line wide width dimension size) same (nm nanometer) same ((laser electron) near5 beam)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:59
L37	1	24 and 36	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 12:59

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L38	2381	pattern\$4 same (line wide width dimension size) with (nm nanometer) same ((laser electron) with beam)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 13:00
L39	1	24 and 38	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 13:00
L40	9312	(line wide width dimension size) with (nm nanometer) same ((laser electron) with beam)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 13:01
L41	1	24 and 40	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 13:00
L42	1	22 and 40	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 13:01
L43	1	10 and 40	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 13:01
L44	448	(line wide width dimension size) with (nm nanometer) same ((laser electron) with beam) and ((organic near2 molecular) (micro adj scale) (nano adj scale))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 13:02
L45	375	44 and ("50" "100" "25" "75" "125" "150") with (nanometer nm)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 13:03
L46	19	44 and ("50" "100" "25" "75" "125" "150") with (nanometer nm) same (electron with etch\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 13:04
L47	2	3 and electron with beam	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 13:22

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L48	2	3 and etch\$4 with pattern\$4 same (laser electron beam)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 13:26
L49	2	3 and (lift "lift off")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/21 13:26